

# Satoshi Hamaguchi

## List of Publications by Year in descending order

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147  
papers

3,493  
citations

257450

24  
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161849

54  
g-index

151  
all docs

151  
docs citations

151  
times ranked

2699  
citing authors

#	ARTICLE	IF	CITATIONS
1	Self-sputtering of the Lennard-Jones crystal. <i>Physics of Plasmas</i> , 2022, 29, 023507.	1.9	4
2	Structural and electrical characteristics of ion-induced Si damage during atomic layer etching. <i>Japanese Journal of Applied Physics</i> , 2022, 61, S11003.	1.5	2
3	Why are physical sputtering yields similar for incident ions with different masses?—physical sputtering yields of the Lennard-Jones system. <i>Journal Physics D: Applied Physics</i> , 2022, 55, 225209.	2.8	3
4	Five-step plasma-enhanced atomic layer etching of silicon nitride with a stable etched amount per cycle. <i>Japanese Journal of Applied Physics</i> , 2022, 61, 066002.	1.5	5
5	Roles of the reaction boundary layer and long diffusion of stable reactive nitrogen species (RNS) in plasma-irradiated water as an oxidizing media — numerical simulation study. <i>Japanese Journal of Applied Physics</i> , 2022, 61, 076002.	1.5	5
6	Development of a Massively Parallelized Fluid-Based Plasma Simulation Code With a Finite-Volume Method on an Unstructured Grid. <i>IEEE Transactions on Plasma Science</i> , 2021, 49, 104-119.	1.3	0
7	Characterization of descriptors in machine learning for data-based sputtering yield prediction. <i>Physics of Plasmas</i> , 2021, 28, .	1.9	21
8	Preface to Special Topic: Invited Papers from the 2nd International Conference on Data-Driven Plasma Science. <i>Physics of Plasmas</i> , 2021, 28, .	1.9	2
9	Monitoring of nonthermal plasma degradation of phthalates by ion mobility spectrometry. <i>Plasma Processes and Polymers</i> , 2021, 18, 2100032.	3.0	3
10	Evaluation of nickel self-sputtering yields by molecular-dynamics simulation. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021, 39, .	2.1	5
11	Surface damage formation during atomic layer etching of silicon with chlorine adsorption. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021, 39, .	2.1	17
12	Molecular dynamics simulation for reactive ion etching of Si and SiO <sub>2</sub> by SF <sub>5</sub> <sup>+</sup> ions. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2021, 39, .	1.2	9
13	Amine modification of calcium phosphate by low-pressure plasma for bone regeneration. <i>Scientific Reports</i> , 2021, 11, 17870.	3.3	4
14	Formation and desorption of nickel hexafluoroacetylacetonate Ni(hfac) <sub>2</sub> on a nickel oxide surface in atomic layer etching processes. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	2.1	12
15	Mechanism of SiN etching rate fluctuation in atomic layer etching. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	2.1	15
16	Experimental and numerical analysis of the effects of ion bombardment in silicon oxide (SiO <sub>2</sub> ) plasma enhanced atomic layer deposition (PEALD) processes. <i>Japanese Journal of Applied Physics</i> , 2020, 59, SJJ A01.	1.5	12
17	On-wafer monitoring and control of ion energy distribution for damage minimization in atomic layer etching processes. <i>Japanese Journal of Applied Physics</i> , 2020, 59, SJJ C01.	1.5	12
18	Stability of hexafluoroacetylacetonone molecules on metallic and oxidized nickel surfaces in atomic-layer-etching processes. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, 022610.	2.1	10

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19	Molecular dynamics simulation of amine groups formation during plasma processing of polystyrene surfaces. <i>Plasma Sources Science and Technology</i> , 2020, 29, 105020.	3.1	9
20	Modeling characterisation of a bipolar pulsed discharge. <i>Plasma Sources Science and Technology</i> , 2020, 29, 104001.	3.1	6
21	Self-limiting processes in thermal atomic layer etching of nickel by hexafluoroacetylacetone. <i>Japanese Journal of Applied Physics</i> , 2020, 59, 090905.	1.5	7
22	Surface Reactions of Plasma assisted Atomic Layer Etching for Silicon. <i>Vacuum and Surface Science</i> , 2020, 63, 616-622.	0.1	1
23	Damage recovery and low damage etching of ITO in H <sub>2</sub> /CO plasma: Effects of hydrogen or oxygen. <i>Plasma Processes and Polymers</i> , 2019, 16, 1900029.	3.0	6
24	Molecular dynamics simulation of Si and SiO <sub>2</sub> reactive ion etching by fluorine-rich ion species. <i>Surface and Coatings Technology</i> , 2019, 380, 125032.	4.8	20
25	Molybdenum Capping Layer Effect on Electromigration Failure of Plasma Etched Copper Lines. <i>ECS Transactions</i> , 2019, 92, 39-46.	0.5	1
26	Effects of excitation voltage pulse shape on the characteristics of atmospheric-pressure nanosecond discharges. <i>Plasma Sources Science and Technology</i> , 2019, 28, 075004.	3.1	8
27	The future for plasma science and technology. <i>Plasma Processes and Polymers</i> , 2019, 16, 1800118.	3.0	160
28	Inter- and Intraspecific Variation in Sex Hormone-Induced Sex-Reversal in Medaka, <i>Oryzias latipes</i> and <i>Oryzias sakaizumii</i> . <i>Zoological Science</i> , 2019, 36, 425.	0.7	6
29	Foundations of low-temperature plasma enhanced materials synthesis and etching. <i>Plasma Sources Science and Technology</i> , 2018, 27, 023001.	3.1	98
30	Cyclic etching of tin-doped indium oxide using hydrogen-induced modified layer. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 06JB02.	1.5	13
31	Preface: Plasma Sources for Biological and Biomaterial Applications. <i>Plasma Medicine</i> , 2018, 8, v.	0.6	0
32	Ion energy and angular distributions in low-pressure capacitive oxygen RF discharges driven by tailored voltage waveforms. <i>Plasma Sources Science and Technology</i> , 2018, 27, 104008.	3.1	31
33	Enhanced etching of tin-doped indium oxide due to surface modification by hydrogen ion injection. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 06JC05.	1.5	8
34	The effect of photoemission on nanosecond helium microdischarges at atmospheric pressure. <i>Plasma Sources Science and Technology</i> , 2018, 27, 054001.	3.1	27
35	Impact of non-thermal plasma surface modification on porous calcium hydroxyapatite ceramics for bone regeneration. <i>PLoS ONE</i> , 2018, 13, e0194303.	2.5	30
36	Effects of hydrogen ion irradiation on zinc oxide etching. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, .	2.1	13

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37	The 2017 Plasma Roadmap: Low temperature plasma science and technology. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 323001.	2.8	710
38	Editorial for achieving atomistic control in plasma–material interactions. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 490201.	2.8	0
39	Etching yields and surface reactions of amorphous carbon by fluorocarbon ion irradiation. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 06HB09.	1.5	11
40	Preface: Sixth International Conference on Plasma Medicine (ICPM-6). <i>Plasma Medicine</i> , 2017, 7, v-vi.	0.6	1
41	Effects of hydrogen-damaged layer on tin-doped indium oxide etching by $H_2/Ar$ plasma. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 06HD02.	1.5	11
42	Molecular dynamics study on fluorine radical multilayer adsorption mechanism during Si, $SiO_2$ , and $Si_3N_4$ etching processes. <i>Japanese Journal of Applied Physics</i> , 2016, 55, 116204.	1.5	14
43	Atmospheric-pressure plasma-irradiation inhibits mouse embryonic stem cell differentiation to mesoderm and endoderm but promotes ectoderm differentiation. <i>Journal Physics D: Applied Physics</i> , 2016, 49, 165401.	2.8	11
44	Generation and transport of liquid-phase reactive species due to plasma-liquid interaction. , 2016, , .		0
45	Mass-selected ion beam study on etching characteristics of ZnO by methane-based plasma. <i>Japanese Journal of Applied Physics</i> , 2016, 55, 021202.	1.5	9
46	Numerical Simulation of Atomic Layer Oxidation of Silicon by Oxygen Gas Cluster Beams. <i>Plasma and Fusion Research</i> , 2015, 10, 1406079-1406079.	0.7	0
47	Indium Implantation onto Zeolite for Development of Novel Catalysts with a Ion Beam System. <i>Journal of Smart Processing</i> , 2015, 4, 228-233.	0.1	1
48	Correlation between dry etching resistance of Ta masks and the oxidation states of the surface oxide layers. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2015, 33, 051810.	1.2	11
49	Mass Spectrometry Analyses of Ions Generated by Atmospheric-Pressure Plasma Jets in Ambient Air. <i>Plasma Medicine</i> , 2015, 5, 283-298.	0.6	12
50	Molecular dynamics simulation of silicon oxidation enhanced by energetic hydrogen ion irradiation. <i>Journal Physics D: Applied Physics</i> , 2015, 48, 152002.	2.8	17
51	Molecular dynamic simulation of damage formation at Si vertical walls by grazing incidence of energetic ions in gate etching processes. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015, 33, .	2.1	15
52	Sputtering yields and surface chemical modification of tin-doped indium oxide in hydrocarbon-based plasma etching. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015, 33, .	2.1	15
53	In Focus: Plasma Medicine. <i>Biointerphases</i> , 2015, 10, 029301.	1.6	18
54	Suboxide/subnitride formation on Ta masks during magnetic material etching by reactive plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015, 33, .	2.1	24

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55	Low Energy Indium or Gallium Ion Implantations to SiO <sub>2</sub> Thin Films for Development of Novel Catalysts. E-Journal of Surface Science and Nanotechnology, 2014, 12, 197-202.	0.4	0
56	Generation of Free Radicals in Liquid by Atmospheric-Pressure Plasmas and its Application to Biology and Medicine. , 2014, , .		7
57	Characterization of polymer layer formation during SiO <sub>2</sub> /SiN etching by fluoro/hydrofluorocarbon plasmas. Japanese Journal of Applied Physics, 2014, 53, 03DD02.	1.5	33
58	Ion beam experiments for the study of plasma-surface interactions. Journal Physics D: Applied Physics, 2014, 47, 224008.	2.8	38
59	Proliferation assay of mouse embryonic stem (ES) cells exposed to atmospheric-pressure plasmas at room temperature. Journal Physics D: Applied Physics, 2014, 47, 445402.	2.8	11
60	Oxidation of nitric oxide by atmospheric pressure plasma in a resonant plasma reactor. Journal Physics D: Applied Physics, 2013, 46, 135202.	2.8	8
61	Surface Modification of Poly(methyl methacrylate) by Hydrogen-Plasma Exposure and Its Sputtering Characteristics by Ultraviolet Light Irradiation. Japanese Journal of Applied Physics, 2013, 52, 090201.	1.5	21
62	Grid-pattern formation of extracellular matrix on silicon by low-temperature atmospheric-pressure plasma jets for neural network biochip fabrication. Applied Surface Science, 2013, 276, 1-6.	6.1	7
63	Quantum cascade laser absorption spectroscopy with the amplitude-to-time conversion technique for atmospheric-pressure plasmas. Journal of Applied Physics, 2013, 113, 213101.	2.5	5
64	Chemically reactive species in liquids generated by atmospheric-pressure plasmas and their roles in plasma medicine. AIP Conference Proceedings, 2013, , .	0.4	22
65	Characteristics of silicon etching by silicon chloride ions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2013, 31, .	2.1	20
66	Hydrogen Plasma Exposure of Polymethylmethacrylate and Etching by Low Energy Ar <sup>+</sup> Ion Beam. Journal of the Vacuum Society of Japan, 2013, 56, 129-132.	0.3	2
67	Sputtering yields of magnesium hydroxide [Mg(OH) <sub>2</sub> ] by noble-gas ion bombardment. Journal Physics D: Applied Physics, 2012, 45, 432001.	2.8	9
68	Sputtering Yields of CaO, SrO, and BaO by Monochromatic Noble Gas Ion Bombardment. Japanese Journal of Applied Physics, 2012, 51, 08HB02.	1.5	14
69	Si Damage Due to Oblique-Angle Ion Impact Relevant for Vertical Gate Etching Processes. Japanese Journal of Applied Physics, 2012, 51, 08HB01.	1.5	8
70	Efficient modification of the surface properties of interconnected porous hydroxyapatite by low-pressure low-frequency plasma treatment to promote its biological performance. Journal Physics D: Applied Physics, 2012, 45, 372001.	2.8	6
71	Sputtering yields and surface modification of poly(methyl methacrylate) (PMMA) by low-energy Ar <sup>+</sup> ion bombardment with vacuum ultraviolet (VUV) photon irradiation. Journal Physics D: Applied Physics, 2012, 45, 505201.	2.8	22
72	Microcavity array plasma system for remote chemical processing at atmospheric pressure. Journal Physics D: Applied Physics, 2012, 45, 222001.	2.8	3

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73	Si Damage Due to Oblique-Angle Ion Impact Relevant for Vertical Gate Etching Processes. Japanese Journal of Applied Physics, 2012, 51, 08HB01.	1.5	16
74	Sputtering Yields of CaO, SrO, and BaO by Monochromatic Noble Gas Ion Bombardment. Japanese Journal of Applied Physics, 2012, 51, 08HB02.	1.5	5
75	Dynamics of Near-Atmospheric-Pressure Hydrogen Plasmas Driven by Pulsed High Voltages. IEEE Transactions on Plasma Science, 2011, 39, 2100-2101.	1.3	4
76	Numerical analyses of hydrogen plasma generation by nanosecond pulsed high voltages at near-atmospheric pressure. Journal Physics D: Applied Physics, 2011, 44, 375201.	2.8	9
77	Rapid Breakdown Mechanisms of Open Air Nanosecond Dielectric Barrier Discharges. Physical Review Letters, 2011, 107, 065002.	7.8	78
78	Micro-pattern formation of extracellular matrix (ECM) layers by atmospheric-pressure plasmas and cell culture on the patterned ECMs. Journal Physics D: Applied Physics, 2011, 44, 482002.	2.8	4
79	Si Recess of Polycrystalline Silicon Gate Etching: Damage Enhanced by Ion Assisted Oxygen Diffusion. Japanese Journal of Applied Physics, 2011, 50, 08KD02.	1.5	9
80	Experimental evaluation of CaO, SrO and BaO sputtering yields by Ne <sup>+</sup> or Xe <sup>+</sup> ions. Journal Physics D: Applied Physics, 2011, 44, 255203.	2.8	18
81	Hydrogen effects in hydrofluorocarbon plasma etching of silicon nitride: Beam study with CF <sup>+</sup> , CF <sub>2</sub> <sup>+</sup> , CHF <sub>2</sub> <sup>+</sup> , and CH <sub>2</sub> F <sup>+</sup> ions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2011, 29, .	2.1	52
82	Improvement of Hydrophilicity of Interconnected Porous Hydroxyapatite by Dielectric Barrier Discharge Plasma Treatment. IEEE Transactions on Plasma Science, 2011, 39, 2166-2167.	1.3	12
83	Si Recess of Polycrystalline Silicon Gate Etching: Damage Enhanced by Ion Assisted Oxygen Diffusion. Japanese Journal of Applied Physics, 2011, 50, 08KD02.	1.5	15
84	Arrangement of PC12 Cells on a Silicon Chip via Extracellular Matrix (ECM) Layer Patterning by Atmospheric Pressure Plasmas. Plasma and Fusion Research, 2011, 6, 1306155-1306155.	0.7	0
85	Plasma-surface Interactions in Material Processing. Journal of Physics: Conference Series, 2010, 257, 012007.	0.4	5
86	Facile Creation of Biointerface on Commodity Plastic Surface by Combination of Atmospheric Plasma and Reactive Polymer Coating. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2010, 23, 579-583.	0.3	1
87	Effects of pH on Bacterial Inactivation in Aqueous Solutions due to Low-temperature Atmospheric Pressure Plasma Application. Plasma Processes and Polymers, 2010, 7, 33-42.	3.0	469
88	Reverse Propagation of Atmospheric Pressure Plasma Jets. Japanese Journal of Applied Physics, 2010, 49, 100209.	1.5	6
89	Molecular dynamics simulation of the formation of $s_p m n^3$ bonds in hydrogenated diamondlike carbon deposition processes. Physical Review E, 2010, 81, 041602.	2.1	30
90	Molecular dynamics simulation study on sputtering of graphite or amorphous carbon by low-energy hydrogen or its isotope ion beams. , 2010, , .		1

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91	Sputtering yields of Au by low-energy noble gas ion bombardment. Journal Physics D: Applied Physics, 2009, 42, 135203.	2.8	24
92	Preparation of Stable Water-Dispersible PEGylated Gold Nanoparticles Assisted by Nonequilibrium Atmospheric-Pressure Plasma Jets. Chemistry of Materials, 2009, 21, 3526-3535.	6.7	89
93	Structure of laboratory ball lightning. Physical Review E, 2009, 80, 067401.	2.1	6
94	Creation of Biointerface by Atmospheric Plasma Treatment of Plasma Sensitive Polymeric Materials. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2009, 22, 481-484.	0.3	3
95	Nonequilibrium Atmospheric Plasma Jets Assisted Stabilization of Drug Delivery Carriers: Preparation and Characterization of Biodegradable Polymeric Nano-Micelles with Enhanced Stability. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2009, 22, 467-471.	0.3	6
96	Effects of Ultraviolet Light Irradiation on Etching of Polymethylmethacrylate by CF <sub>3</sub> <sup>+</sup> Ion Beam Injections. Journal of the Vacuum Society of Japan, 2009, 52, 127-130.	0.3	0
97	Magnetized microdischarge plasma generation at low pressure. Thin Solid Films, 2008, 516, 6668-6672.	1.8	1
98	Experimental evaluation of MgO sputtering yields by monochromatic Ne, Kr, or Xe ion beams. Thin Solid Films, 2008, 517, 835-840.	1.8	31
99	Molecular dynamics simulation of microcrystalline Si deposition processes by silane plasmas. Thin Solid Films, 2008, 516, 3443-3448.	1.8	6
100	Molecular dynamics simulations for nitridation of organic polymer surfaces due to hydrogen <sup>+</sup> nitrogen ion beam injections. Thin Solid Films, 2008, 516, 3449-3453.	1.8	6
101	Plasma generation inside externally supplied Ar bubbles in water. Plasma Sources Science and Technology, 2008, 17, 025006.	3.1	58
102	Nonlinear Evolution of Pressure Gradient Driven Modes and Anomalous Transport in Plasmas. AIP Conference Proceedings, 2008, , .	0.4	0
103	Reducing Damage to Si Substrates during Gate Etching Processes. Japanese Journal of Applied Physics, 2008, 47, 5324.	1.5	111
104	Design of Biointerface by Nonequilibrium Atmospheric Plasma Jets-Approach from Plasma Susceptible Polymers-. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2008, 21, 267-270.	0.3	4
105	Journal of Applied Physics, 2008, 103, 043301.		
106	Journal of the Vacuum Society of Japan, 2009, 52, 127-130.		
107	Atomic-Scale Analyses of Non-Equilibrium Surface Reactions During Plasma Processing. ECS Transactions, 2007, 8, 185-190.	0.5	0
108	Temporal Evolution of Ion Fragment Production from Dimethylsilane by a Hot Tungsten Wire and Compounds Deposited on the Tungsten Surface. Japanese Journal of Applied Physics, 2007, 46, 1707-1709.	1.5	5

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109	Measurement of Magnesium Oxide Sputtering Yields by He and Ar Ions with a Low-Energy Mass-Selected Ion Beam System. Japanese Journal of Applied Physics, 2007, 46, L1132-L1134.	1.5	25
110	Molecular Dynamics Simulations of Organic Polymer Dry Etching at High Substrate Temperatures. Japanese Journal of Applied Physics, 2007, 46, 1692-1699.	1.5	14
111	Dynamics of resistive double tearing modes with broad linear spectra. Physics of Plasmas, 2007, 14, 022107.	1.9	19
112	Molecular dynamics simulation study on substrate temperature dependence of sputtering yields for an organic polymer under ion bombardment. Journal of Applied Physics, 2007, 101, 046108.	2.5	18
113	Synthesis of Uniformly Dispersed Metal Nanoparticles with Dispersion Stability by Nonequilibrium Atmospheric Plasma Jets. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2007, 20, 229-233.	0.3	12
114	Time evolution of electrode voltage distribution in large-area capacitively coupled plasmas. Thin Solid Films, 2007, 515, 5188-5192.	1.8	1
115	MD simulations of amorphous SiO <sub>2</sub> thin film formation in reactive sputtering deposition processes. Thin Solid Films, 2007, 515, 4879-4882.	1.8	44
116	Atomic-level simulation of non-equilibrium surface chemical reactions under plasma-wall interaction. Computer Physics Communications, 2007, 177, 108-109.	7.5	4
117	Molecular dynamics simulation analyses on injection angle dependence of SiO <sub>2</sub> sputtering yields by fluorocarbon beams. Thin Solid Films, 2007, 515, 4883-4886.	1.8	21
118	Numerical Analysis of Incident Angle Effects in Reactive Sputtering Deposition of Amorphous SiO <sub>2</sub> . Japanese Journal of Applied Physics, 2006, 45, 8163-8167.	1.5	7
119	Molecular dynamics study on Ar ion bombardment effects in amorphous SiO <sub>2</sub> deposition processes. Journal of Applied Physics, 2006, 100, 123305.	2.5	20
120	Fragment Ions of Dimethylsilane Produced by Hot Tungsten Wires. Japanese Journal of Applied Physics, 2006, 45, 8204-8207.	1.5	35
121	Fragment Ions of Methylsilane Produced by Hot Tungsten Wires. Japanese Journal of Applied Physics, 2006, 45, 1813-1815.	1.5	17
122	Radio-Frequency-Driven Atmospheric-Pressure Plasmas in Contact with Liquid Water. Japanese Journal of Applied Physics, 2006, 45, 8294-8297.	1.5	38
123	Nonlinear evolution of the m=1 internal kink mode in the presence of magnetohydrodynamic turbulence. Physics of Plasmas, 2006, 13, 032506.	1.9	6
124	Fast growing double tearing modes in a tokamak plasma. Physics of Plasmas, 2005, 12, 082504.	1.9	52
125	Nonlinear Evolution of q=1 Triple Tearing Modes in a Tokamak Plasma. Physical Review Letters, 2005, 94, 065001.	7.8	65
126	Numerical analyses of surface interactions between radical beams and organic polymer surfaces. Plasma Physics and Controlled Fusion, 2005, 47, A11-A18.	2.1	16



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127	Molecular-dynamics simulations of organic polymer etching by hydrocarbon beams. Journal of Applied Physics, 2004, 96, 6147-6152.	2.5	36
128	Shear flow generation due to electromagnetic instabilities. Nuclear Fusion, 2003, 43, 63-67.	3.5	1
129	Nonlinear behaviour of resistive drift-Alfvén instabilities in a magnetized cylindrical plasma. Plasma Physics and Controlled Fusion, 2002, 44, 1689-1705.	2.1	6
130	Effect of poloidal shear flow on local flattening of density profile due to nonlinear resistive interchange mode. Plasma Physics and Controlled Fusion, 2002, 44, A507-A515.	2.1	0
131	Advances in Dusty Plasmas. Strongly Coupled Dusty Plasmas.. Journal of Plasma and Fusion Research, 2002, 78, 313-319.	0.4	1
132	Comparison between Double-Resonant and Non-Resonant Mode Driven Convections in a Stellarator with a Non-Monotonic Rotational Transform. Journal of the Physical Society of Japan, 2001, 70, 983-987.	1.6	1
133	Nonlinear Double Tearing Mode in Negative Shear Cylindrical Tokamaks. Journal of the Physical Society of Japan, 2001, 70, 2578-2587.	1.6	5
134	Plasma Current Effects on Unstable Resistive Drift-Alfvén Modes in a Magnetized Cylindrical Plasma. Journal of the Physical Society of Japan, 2001, 70, 3197-3200.	1.6	1
135	Resistive Drift-Alfvén Instability in a Cylindrical Plasma. Journal of the Physical Society of Japan, 2000, 69, 1401-1408.	1.6	6
136	Numerical Simulation of Etching and Deposition Processes. Japanese Journal of Applied Physics, 1997, 36, 4762-4768.	1.5	20
137	New fluid model for the turbulent transport due to the ion temperature gradient. Physics of Fluids B, 1993, 5, 1516-1522.	1.7	15
138	Analysis of a kinematic model for ion transport in rf plasma sheaths. Physical Review A, 1992, 45, 5913-5928.	2.5	12
139	Self-consistent Monte Carlo simulation of the cathode fall including treatment of negative-glow electrons. Physical Review A, 1992, 46, 1066-1077.	2.5	20
140	Monte Carlo simulations of space-charge-limited ion transport through collisional plasma sheaths. Physical Review A, 1991, 44, 2664-2681.	2.5	42
141	Nonlinear behavior of magnetohydrodynamic modes near marginally stable states. II. Application to the resistive fast interchange mode. Physics of Fluids B, 1990, 2, 1184-1189.	1.7	2
142	Fluctuation spectrum and transport from ion temperature gradient driven modes in sheared magnetic fields. Physics of Fluids B, 1990, 2, 1833-1851.	1.7	86
143	Ion temperature gradient driven turbulence in the weak density gradient limit. Physics of Fluids B, 1990, 2, 3040-3046.	1.7	12
144	Anomalous transport arising from nonlinear resistive pressure-driven modes in a plasma. Physics of Fluids B, 1989, 1, 1416-1430.	1.7	22

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145	Selective Acceleration of NBI-injected Fast Ions by Ion Cyclotron Wave in a Tokamak Plasma. Japanese Journal of Applied Physics, 1986, 25, 1045-1048.	1.5	0
146	Helically Assisted Low-q Tokamak with $l=2$ Helical Winding. Japanese Journal of Applied Physics, 1984, 23, L505-L508.	1.5	0
147	Low-energy ion irradiation effects on chlorine desorption in plasma-enhanced atomic layer deposition (PEALD) for silicon nitride. Japanese Journal of Applied Physics, 0, , .	1.5	0